Abstract

CLEANING METHOD FOR A LIFT PIN AND SUBSTRATE PROCESSING APPARATUS

A cleaning method for a lift pin is a cleaning method for a lift pin in a substrate processing apparatus that includes a rotating plate, a plurality of supporting units, a liquid discharge unit, and a plurality of lift pins and includes a supporting step and a cleaning step. The rotating plate is rotatable. The plurality of supporting units are provided on the rotating plate and support a substrate. The liquid discharge unit discharges a cleaning liquid to a top surface of the substrate that is supported by the plurality of supporting units. The plurality of lift pins respectively pass through a plurality of passage units that are provided on the rotating plate and push the substrate upward. The supporting step supports the substrate by using the plurality of supporting units. The cleaning step discharges the cleaning liquid from the liquid discharge unit to the top surface of the substrate that is supported by the plurality of supporting units in a state where the plurality of lift pins are arranged at positions that are lower than the rotating plate, so as to clean the plurality of lift pins with the cleaning liquid that flows down from the plurality of passage units.

Fig. 2